

## Claims

1. A device for examining contact state of films, comprising:

photographing means for photographing the image of a prescribed pattern irradiated with transparent light which is radiated by a light source from the other surface side of a first film and goes through the first film and a second film in order, from the other surface side of the second film, under such a condition that one surface having the light scattering property of the second film faces and contacts one surface having the prescribed pattern recorded thereon of the first film; and

display means for displaying the image of the prescribed pattern photographed by said photographing means.

2. The device for examining contact state of films according to Claim 1, wherein

said device for examining contact state of films comprises:

waveform pattern creating means for creating a waveform pattern based on a luminance level in the image of the prescribed pattern photographed by said photographing means; and

overlaying means for overlaying the waveform pattern on the prescribed pattern.

3. The device for examining contact state of films according to Claim 1, wherein

said device for examining contact state of films comprises:

luminance level calculating means for calculating the average of a luminance level in the image of the prescribed pattern photographed by said photographing means; and

luminance level display means for numerically displaying the average of the luminance level calculated by said luminance level calculating means.

4. The device for examining contact state of films according to Claim 1, wherein

the prescribed pattern is a stripe pattern in which a high transparent part having a high light transparent property and a low transparent part having a low light transparent property are linearly and alternately laid in a running direction of the first film and the second film.

5. The device for examining contact state of films according to Claim 1, wherein

said device for examining contact state of films comprises

control means for controlling said photographing means to shift in a width direction of the first film and the second film.

6. A device for examining contact state of films, comprising:

photographing means for photographing the image of a prescribed pattern irradiated with a transparent light which is radiated by a light source from the other surface of a first film and goes through the first film and a second film in order, from the other surface side of the second film, under such a condition that one surface having the light scattering property of the second film faces and contacts one surface having the prescribed pattern recorded thereon of the first film;

waveform pattern creating means for creating a waveform pattern based on a luminance level in the image of the prescribed pattern photographed by said photographing means; and

display means for displaying the waveform pattern based on the luminance level.

7. The device for examining contact state of films according to Claim 6, wherein

said device for examining contact state of films comprises

overlaying means for overlaying the image of the prescribed pattern photographed by said photographing means on the waveform pattern.

8. The device for examining contact state of films according to Claim 6, wherein

said device for examining contact state of films comprises

luminance level calculating means for calculating the average of a luminance level in the image of the prescribed pattern photographed by said photographing means; and

luminance level display means for numerically displaying the average of the luminance level calculated by said luminance level calculating means.

9. The device for examining contact state of films according to Claim 6, wherein

the prescribed pattern is a stripe pattern in which a high transparent part having a high light transparent property and a low transparent part having a low light transparent property are linearly and alternately laid in a running direction of the first film and the second film.

10. The device for examining contact state of films according to Claim 6, wherein

said device for examining contact state of films comprises control means for controlling said photographing means to shift in a width direction of the first film and the second film.

11. A method of examining contact state of films, comprising:  
a photographing step of photographing the image of a prescribed pattern irradiated with a transparent light which is

radiated by a light source from the other surface side of a first film and goes through the first film and a second film in order, from the other surface side of the second film, under such a condition that one surface having the light scattering property of the second film faces and contacts one surface having the prescribed pattern recorded thereon of the first film; and

a display step of displaying the image of the prescribed pattern photographed by said photographing step.

12. The method of examining contact state of films according to Claim 11, wherein

said method of examining contact state of films comprises:

a waveform pattern creating step of creating a waveform pattern based on a luminance level in the image of the prescribed pattern photographed by said photographing step; and

an overlaying means for overlaying the waveform pattern on the prescribed pattern.

13. The method of examining contact state of films according to Claim 11, wherein

said method of examining contact state of films comprises:

a luminance level calculating step of calculating the average of a luminance level in the image of the prescribed

pattern photographed by said photographing step; and

a luminance level display means for numerically displaying the average of the luminance level calculated by said luminance level calculating step.

14. The method of examining contact state of films according to Claim 11, wherein

the prescribed pattern is a stripe pattern in which a high transparent part having a high light transparent property and a low transparent part having a low light transparent property are linearly and alternately laid in a running direction of the first film and the second film.

15. A method of examining contact state of films, comprising

a photographing step of photographing the image of a prescribed pattern irradiated with a transparent light which is radiated by a light source from the other surface side of a first film and goes through the first film and a second film in order, from the other surface side of the second film, under such a condition that one surface having the light scattering property of the second film faces and contacts one surface having the prescribed pattern recorded thereon of the first film;

a waveform pattern creating step of creating a waveform pattern based on a luminance level in the image of the

prescribed pattern photographed by said photographing step; and  
a display step of displaying the waveform pattern based on  
the luminance level.

16. The method of examining contact state of films according to  
Claim 15, wherein

said method of examining contact state of films comprises  
an overlaying step of overlaying the image of the  
prescribed pattern photographed by said photographing step  
on the waveform pattern.

17. The method of examining contact state of films according to  
Claim 15, wherein

said method of examining contact state of films comprises  
a luminance level calculating step of calculating the  
average of a luminance level in the image of the prescribed  
pattern photographed by said photographing step; and  
a luminance level display step of numerically  
displaying the average of the luminance level calculated by  
said luminance level calculating step.

18. The method of examining contact state of films according to  
Claim 15, wherein

the prescribed pattern is a stripe pattern in which a high  
transparent part having a high light transparent property and a

low transparent part having a low light transparent property are linearly and alternately laid in a running direction of the first film and the second film.

19. A film for examination used in a device for examining contact state of films to examine the contact state of piled films, comprising

in the case of examining the contact state using the photographing result obtained by photographing the image irradiated with a transparent light which is radiated by a light source from the film for examination side and goes through the film for examination and a second film in order, under such a condition that said film for examination and the second film are piled in said device for examining contact state of films,

a pattern of a plurality of stripes formed in a running direction of films on one surface of said film for examination which has to face and contact one surface having the light scattering property of the second film.

20. The film for examination according to Claim 19, wherein

the stripe pattern is a stripe pattern in which a high transparent part having a high light transparent property and a low transparent part having a low light transparent property are alternately, periodically and linearly laid with the same width in the running direction of films.



21. The film for examination according to Claim 19, wherein  
the stripe pattern is a stripe pattern in which a high  
transparent part having a high light transparent property and a  
low transparent part having a low light transparent property are  
alternately, irregularly and linearly laid with different widths  
in the running direction of films.

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